

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION N	NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/537,259		05/31/2005	Wu-Song Huang	FIS920020051US1	1422
32074	7590	06/29/2006		EXAMINER	
INTERNATIONAL BUSINESS MACHINES CORPORATION				LETSCHER, GERALDINE	
DEPT. 18 BLDG. 3				ART UNIT	PAPER NUMBER
2070 ROUTE 52				1752	
HOPEWELL JUNCTION, NY 12533			DATE MAILED: 06/29/2006		

Please find below and/or attached an Office communication concerning this application or proceeding.

			7
	Application N .	Applicant(s)	
	10/537,259	HUANG ET AL.	
Office Action Summary	Examin r	Art Unit	
	Geraldine V. Letscher	1752	
The MAILING DATE of this communication app Period for Reply	ears on the cover she t with the	c rrespondenc address	
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tinuity iii apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	N. mely filed the mailing date of this communication. ED (35 U.S.C. § 133).	
Status			
1) Responsive to communication(s) filed on 31 M	action is non-final. nce except for formal matters, pre-		
Disposition of Claims			
4) ☐ Claim(s) 1-15 is/are pending in the application. 4a) Of the above claim(s) is/are withdray 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-15 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or	vn from consideration.		
Application Papers			
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) access applicant may not request that any objection to the Replacement drawing sheet(s) including the correct and the correct and the correct access access and the correct an	epted or b) objected to by the drawing(s) be held in abeyance. Se ion is required if the drawing(s) is ob	e 37 CFR 1.85(a). ojected to. See 37 CFR 1.121(d)	
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicat rity documents have been receiv ı (PCT Rule 17.2(a)).	ion No ed in this National Stage	
Attachment(s)			
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 5-13-05. S. Patent and Trademark Office	4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal F 6) Other:		

U.S. Patent and Trademark Off PTOL-326 (Rev. 7-05)

Office Acti n Summary ARALDINE ETSCHER Paper No./Mail Date 20060625
RIMARY EXAMINER
ROUP 1100

Application/Control Number: 10/537,259

Art Unit: 1752

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 2. Claims 1-15 are rejected under 35 U.S.C. 102(b) as being anticipated by any one of Hayase et al. (U.S. Patent No. 5,403,695), Hayase et al. (U.S. Patent No. 5,580,702), or Kimura (U.S. Patent No. 5,679,497).

Each of Hayase et al. ('695), Hayase et al. ('702) and Kimura disclose a resist composition and corresponding method of forming a patterned material structure on a substrate said material being selected from the group consisting of organic dielectrics, semiconductors, ceramics and metals, characterized in that said resist composition comprises (a) an imaging polymer, and (b) a radiation sensitive acid generator component, said radiation sensitive acid generator component comprising: (i) a first radiation sensitive acid generator selected from the group consisting of dissolution-inhibiting acid generators, and (ii) a second radiation sensitive acid generator selected from the group consisting of unprotected acidic group-functionalized radiation sensitive

Application/Control Number: 10/537,259 Page 3

Art Unit: 1752

acid generators and acid labile group-protected acidic group-functionalized radiation sensitive acid generators.

3. Claims 1-15 are rejected under 35 U.S.C. 102(e) as being anticipated by Endo et al. (U.S. Patent No. 6,949,329).

Endo et al. discloses resist composition and corresponding method of forming a patterned material structure on a substrate said material being selected from the group consisting of organic dielectrics, semiconductors, ceramics and metals, characterized in that said resist composition comprises (a) an imaging polymer, and (b) a radiation sensitive acid generator component, said radiation sensitive acid generator component comprising: (i) a first radiation sensitive acid generator selected from the group consisting of dissolution-inhibiting acid generators, and (ii) a second radiation sensitive acid generator selected acidic group-functionalized radiation sensitive acid generators and acid labile group-protected acidic group-functionalized radiation sensitive acid generators.

4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Geraldine V. Letscher whose telephone number is (571) 272-1334. The examiner can normally be reached 8:00am to 4:30pm.

GERALDINE LETSCHER
PRIMARY EXAMINER
GROUP 1100

Glise V fed

Art Unit: 1752

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly can be reached on (571) 272-1526. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.